

Search Notes

Application/Control No.

10/617,682

Examiner

D. Rutledge

Applicant(s)/Patent under
Reexamination

AKUTSU ET AL.

Art Unit

2851

SEARCHED

Class	Subclass	Date	Examiner
355	53, 67, 72, 75	3/25/2005	DR
250	491.1	3/25/2005	DR
250	492.2	3/25/2005	DR
310	10, 12	3/25/2005	DR

INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner
355	53,67,75	3/25/2005	DR
250	491.1	3/25/2005	DR
250	492.2	3/25/2005	DR
310	10, 12	3/25/2005	DR

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
electron adj beam, plural\$3 or multiple; (wafer or substrate); stage or table; interferomet\$3 or measur\$5;	3/25/2005	DR
position or location or align\$4; rotating or rotation\$2; direction; z adj axis; measuring adj (light or beam) near4	3/25/2005	DR
perpendicular near4 electron adj beam	3/25/2005	DR